

Silicon Photonic Bragg-Grating add-drop filters and multiplexers using UV lithography

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Abstract: Next generation short reach communication systems require high-performance and low cost optical filters for wavelength division multiplexing. We measured performance of add-drop filters fabricated using a CMOS compatible process. C-band and O-band

Novelty:

1. Rib structure
2. Small features at 1310
3. Large BW and low sidelobes with apodization
4. 1550
5. WDM 4 channels and 2 channels
6. optical litho

1. Introduction

Challenges and state of the art

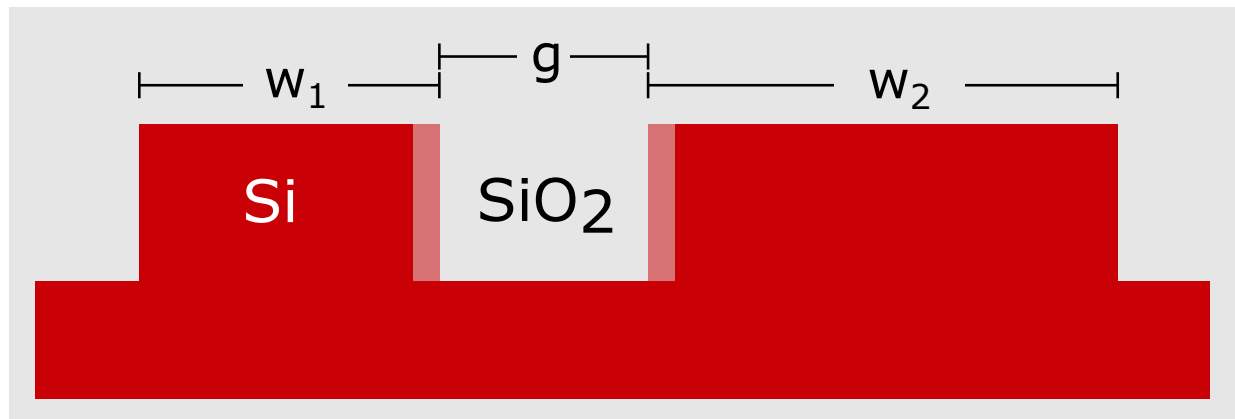


Fig. 1. Cross-section

Acknowledgments

We acknowledge CMC Microsystems for the software and the fabrication subsidy. The authors acknowledge the Natural Sciences and Engineering Research Council of Canada for funding this research. This work is part of the SPEED research project (Silicon Photonic Electrically Engineered Devices) funded by NSERC (RDCPJ438811-12), PROMPT (PJT-2011-17), and TeraXion.